



PATENT  
Attorney Docket No. 7363.0010

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Reissue Application of: )

U.S. Patent No.: 5,792,261 )

Inventor: Kiichi HAMA et al. )

Issued: August 11, 1998 )

Serial No.: 09/478,370 )

Filed: January 6, 2000 )

For: PLASMA PROCESS  
APPARATUS )

Group Art Unit: 1763

Examiner: Alejandro Mulero, L.

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Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

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AMENDMENT

In response to the Office Action dated March 27, 2001, the period for response having been extended one month by the attached petition and requisite fee, please amend this application as follows:

IN THE CLAIMS:

17. (Amended) An apparatus for processing a process region of a substrate, using a plasma, comprising:
- a container substantially formed of a conductive material;
  - a partition plate supported by said container and defining an air-tight process container portion and an air-tight auxiliary container portion, and having a window plate made of dielectric;

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